What is Claimed is:

1. A heating device for heating a susceptor in a semiconductor chamber, comprising:

a central region and multiple annular regions sequentially surrounding the central region outward from the central region, all of which are coaxial with a central axis of the susceptor;

wherein the heating device is disposed on one side of the susceptor;

multiple heating lamps evenly distributed along a circumferential direction in each of the annular regions;

an annular reflective plate disposed on a side of the multiple heating lamps away from the susceptor in each of the annular regions; and

a reflective assembly disposed on one of the annular regions at a side adjacent to the central region in each of the annular regions, wherein the reflective assembly comprises multiple reflective plates in one-to-one correspondence with the heating lamps in said annular region;

wherein the reflective plates extend from the annular reflective plate toward the susceptor so as to guide a light emitted from the corresponding heating lamp to irradiate within a preset area of the susceptor;

wherein the reflective assembly enables the multiple heating lamps to respectively irradiate preset areas of the susceptor in different radial ranges; and wherein a central axis of the annular region is coaxial with a central axis of the susceptor.

2. The heating device of claim 1, wherein each of the reflective plates in the reflective assembly is parallel to the central axis of the susceptor; or,

wherein an included angle between each of the reflective plates and the central axis of the susceptor is the same.

3. The heating device according to claim 2, wherein the heating lamps loaded in the same annular region are disposed at the same height;

wherein when the heating lamps perform heating, a distance between one end of the reflective plate adjacent to the susceptor and the susceptor is a first height of the reflective plate, and the first heights of the reflective plates in the same reflective assembly are different.

4. The heating device according to claim 3, wherein the first heights of any two adjacent reflective plates in the same reflective assembly are different.

5. The heating device according to claim 3, further comprising an actuator configured to adjust lifting of each of the reflective plates.

6. The heating device according to claim 2, wherein the heating lamps in the same annular region are of a same height;

wherein when the heating lamps perform heating, a distance between one end of the reflective plate adjacent to the susceptor and the susceptor is a first height of the reflective plate, and the first heights of the reflective plates in the same reflective assembly are a same; and

wherein in each reflective assembly, at least a part of the reflective plates are provided with light-transmitting holes, and a distance between each of the light-

transmitting holes and the susceptor is less than a distance between the corresponding heating lamp and the susceptor.

7. The heating device of claim 6, wherein in each reflective assembly, distances from two adjacent light-transmitting holes to the susceptor are different.

8. The heating device according to any one of claims 1 to 7, wherein in two adjacent annular regions, along a same radial direction, a distance between the heating lamp in an outer annular region and the susceptor is less than a distance between the heating lamp in an inner annular region and the susceptor.

9. The heating device according to any one of claims 1 to 7, wherein in the two adjacent annular regions, along the same radial direction, a first height of the reflective plate in an outer annular region is less than the first height of the reflective plate in an inner annular region.

10. The heating device according to any one of claims 1 to 7, wherein in each of the annular regions, the reflective assembly is symmetrical with respect to a center of the annular region.

11. The heating device according to any one of claims 3 to 7, further comprising a circular reflective plate disposed in the central region, wherein the reflective assembly in an innermost annular region is arranged around the circular reflective plate; and

a distance of the circular reflective plate from the susceptor is greater than a first

height of any of the reflective plates in the reflective assembly disposed in the innermost annular region.

12. A semiconductor processing apparatus comprising a semiconductor chamber, further comprising a heating device according to any one of claims 1 to 11 disposed above and/or below the semiconductor chamber, wherein the heating device is configured to heat a susceptor within the semiconductor chamber during processing.